

	Hit s	Search Text	DBs
19	27	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and (modulat\$4 or (spatial near14 modulat\$4) or SLM or deflect\$4 or acousto\$6) and ((immers\$4 near12 (liquid or fluid)) same (inlet or outlet or port or input or output))	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
20	10	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and (modulat\$4 or (spatial near14 modulat\$4) or SLM or deflect\$4 or acousto\$6) and ((immers\$4 near9 (liquid or fluid)) and ((capillary near9 force) or capillarit\$3))	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
21	44	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and (modulat\$4 or (spatial near14 modulat\$4) or SLM or deflect\$4 or acousto\$6) and ((immers\$4 near12 (liquid or fluid)) same (inlet or outlet or port or input or output or passag\$5))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB